WEST Search History

| Hide Items | Restore | Clear | Cancel |

DATE: Tuesday, January 29, 2008

Hide?	Set Name	Query	Hit Count
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L35	L32 and @pd > 20080129	0
☐	L34	US-7070915-B2.did.	1
☐	L33	US-7070915-B2.did.	1
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
☐	L32	L29 same surfactant	0
☐	L31	L27 same (cleaning or removing)	0
☐	L30	L27 same L21	0
☐	L29	L16 same L20	0
☐	L28	L16 same surfactant	0
☐	L27	L16 with surfactant	0
		DB=PGPB; PLUR=YES; OP=ADJ	
☐	L26	US-20050205108-A1.did.	1
☐	L25	US-20050205108-A1.did.	1
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
☐	L24	L21 with L19 with L18	1
☐	L23	fluid adj10 surfactant	8358
☐	L22	wafer or semiconductor	2110371
☐	L21	lens or (optical lens)	872335
☐	L20	cleaning or rinsing	1012418
☐	L19	L16 or (ILS)	2104915
☐	L18	immersion lithography system	294
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L17	US-7070915-B2.did.	1
☐	L16	US-7070915-B2.did.	1
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
☐	L15	L14 same surfactant	1
☐	L14	L12 same (cleaning or removing)	21
☐	L13	L12 same l6	2
☐	L12	l1 same l5	189
☐	L11	l1 same surfactant	6
☐	L10	l1 with surfactant	2

DB=PGPB; PLUR=YES; OP=ADJ

☐	L9	US-20050205108-A1.did.	1
☐	L8	US-20050205108-A1.did.	1

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

☐	L7	L6 with L4 with L3	4
☐	L6	fluid adj10 surfactant	8358
☐	L5	wafer or semiconductor	2110371
☐	L4	lens or (optical lens)	872335
☐	L3	cleaning or rinsing	1012418
☐	L2	L1 or (ILS)	2105161
☐	L1	immersion lithography system	294

END OF SEARCH HISTORY